

Large perpendicular magnetic anisotropy in sputter-deposited $\text{Fe}_{100-x}\text{Al}_x/\text{MgAl}_2\text{O}_4$ heterostructures

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Large perpendicular magnetic anisotropy (PMA) at ferromagnet (FM)/oxide interfaces is of utmost importance for magnetic tunnel junctions (MTJ) based memory devices such as spin-transfer torque magnetoresistive random access memory (STT-MRAM) and magneto-electric RAM. In recent publications, Al diffusion from a Co_2FeAl FM layer into an MgAl_2O_4 layer was reported to induce large PMA energy $K_{\text{eff}} = 0.4 \text{ MJ/m}^3$ in lattice-matched $\text{Co}_2\text{FeAl}/\text{MgAl}_2\text{O}_4(001)$ epitaxial heterostructures.^{1,2)} It was suggested that the element diffusion resulted in strong hybridization of Fe- with O-orbitals at their interface, assisting the PMA contribution.²⁾ In order to improve K_{eff} further, we examined the bcc Fe-Al with Fe rich compositions as an FM layer. Here, we report larger PMA energy K_{eff} over 1 MJ/m^3 using ultrathin $\text{Fe}_{100-x}\text{Al}_x/\text{MgAl}_2\text{O}_4$ heterostructures for various x .

The following stack structures were deposited on $\text{MgO}(001)$ single crystal substrates using an ultrahigh vacuum magnetron sputtering system: MgO substrate/ $\text{Cr}(40)/\text{Fe}_{100-x}\text{Al}_x$ (t_{FeAl})/ $\text{Mg}(0.2)/\text{Mg}_{40}\text{Al}_{60}(0.7)$ /plasma oxidation/ $\text{Ru}(2)$ (thickness in nm). The MgO substrate/ Cr layer was annealed at 750°C for 1 h. $\text{Fe}_{100-x}\text{Al}_x$ was deposited by co-sputtering of Fe and Al. An MgAl_2O_4 layer was formed by the plasma oxidation of the $\text{Mg}/\text{Mg}_{40}\text{Al}_{60}$ bilayer. The stacks were post-annealed *ex-situ* at temperatures of T_{ann} . Magnetic properties including K_{eff} were evaluated using a vibrating sample magnetometer at room temperature.

As shown in Fig. 1, large K_{eff} above 1 MJ/m^3 was obtained for $x = 11, 20,$ and 28 , which was nearly the same value observed in $\text{Fe}/\text{MgAl}_2\text{O}_4$ fabricated by electron-beam deposition.³⁾ For $T_{\text{ann}} < 300^\circ\text{C}$, K_{eff} increases with x . K_{eff} values show a strong T_{ann} dependence above 300°C ($x \leq 20$), showing possible tunability of PMA properties with Al concentration and T_{ann} . Scanning transmission electron microscope analysis showed a lattice-matched interface with Al diffusion from the Fe-Al layer into the barrier. Above 300°C , diffusion of Cr was also confirmed; however, we observed no significant change in the saturation magnetization and negligible magnetic dead-layer. The results show very large interfacial PMA can be achieved by atomically-controlling element diffusion in sputter-deposited heterostructures. Therefore, the $\text{Fe}_{100-x}\text{Al}_x/\text{MgAl}_2\text{O}_4$ is a good candidate for future spintronic applications. This study was supported by the ImPACT Program, and JSPS KAKENHI Grant Nos. 16H06332 and 16H03852.

Reference

- 1) H. Sukegawa *et al.*, Appl. Phys. Lett. **110**, 112403 (2017).
- 2) J.P. Hadorn *et al.*, Acta Mater. **145**, 306 (2018).
- 3) Q. Xiang *et al.*, Appl. Phys. Express **11**, 063008 (2018).

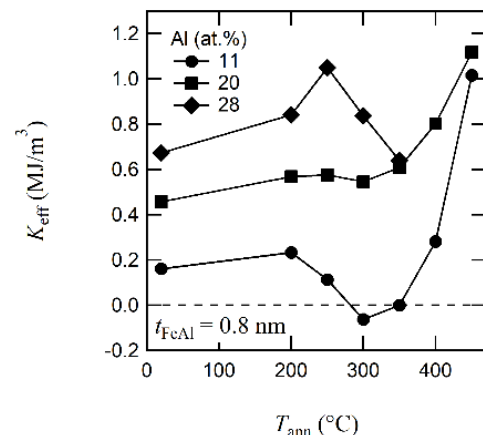


Fig. 1. T_{ann} dependence of K_{eff} of various Al concentration (x) in $\text{Fe}_{100-x}\text{Al}_x$ ($t_{\text{FeAl}} = 0.8 \text{ nm}$)/ MgAl_2O_4 heterostructures.